



Patent claims

An arrangement (1)

comprising a component (2) and at least one monitoring device (3) for recording degradation (5) component (2),

in which the monitoring device (3) has at least one electrically conductive monitoring structure (4) which is decoupled from a function of the component and has a

10 defined electrical property, and in which the component (2) and the monitoring structure

(4) are fixedly connected to one another in such a manner

that the degradation (5) of the component (2) causes 15 degradation (17) of the monitoring structure (4) and therefore a change in the defined electrical property of the monitoring structure (4),

characterized in that

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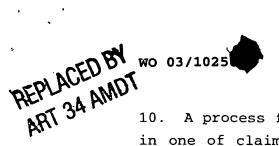
the monitoring device (3) and the monitoring structure (4) are not permanently electrically connected to one another.

- 25 The arrangement as claimed in claim 1, in which the degradation (5) of the component and/or degradation (17) of the monitoring structure selected from the group consisting of deformation and/or removal of material and/or crack formation and/or crack propagation. 30
 - The arrangement as claimed in claim 1 or 2, which the monitoring structure (4) has at least one electrical resonant circuit (7).



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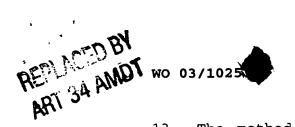
- 4. The arrangement as claimed in one of claims 1 to 3, in which the monitoring structure (4) includes at least one electrically conductive conductor material selected from the group consisting of metallic conductors and/or ceramic conductors.
- The arrangement as claimed in claim 4, in which a component material of the component and the conductor
 material of the monitoring structure have a substantially identical mechanical property.
- The arrangement as claimed in claim 5, in which the mechanical property is selected at least from the group consisting of thermal expansion behavior and/or fracture toughness.
- 7. The arrangement as claimed in one of claims 1 to 6, in which the monitoring structure (4) is arranged at 20 a surface portion (10) of the component (2) and/or in the volume of the component (2).
- 8. The arrangement as claimed in one of claims 1 to 7, in which the component (2) is a heat shield of a combustion chamber.
- 9. The arrangement as claimed in claim 8, in which the monitoring structure (4) is arranged at a surface portion (10) of the heat shield (2) which is remote 30 from an interior space (6) of the combustion chamber.



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- 10. A process for producing the arrangement as claimed in one of claims 1 to 9, comprising the process steps of:
- a) arranging the component (2) and the monitoring structure (4) against one another, and
 - b) fixedly connecting the component and the monitoring structure (4),
- c) providing a monitoring device (3) which is not permanently electrically connected to the monitoring
 device (4).
- 11. The process as claimed in claim 10, in which a ceramic is used as component material of the component and/or as conductor material of the monitoring structure, and joint sintering of the component and the monitoring structure is carried out to fixedly connect the component and the monitoring structure.
- 12. A method for checking the ability of a component20 (1) to function using the arrangement as claimed in one of claims 1 to 9, comprising the method steps of:
 - a) determining an actual value of at least one defined electrical property of the monitoring structure
 - (4) by means of the monitoring device (3), with an
- electrical or electromagnetic coupling being produced between monitoring structure (4) and monitoring device (3),
- b) comparing the actual value of the electrical property with a desired value, representing the ability30 of the component (1) to function, of the electrical property.



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- 13. The method as claimed in claim 12, in which the defined electrical property of the monitoring structure is selected from the group consisting of DC resistance and/or impedance and/or radiofrequency resonance property.
- 14. The method as claimed in claim 12 or 13, in which the determination of the actual value of the defined electrical property is carried out in an operating phase of the component and/or in a stationary phase of the component.